

Polishing composition

Publication number: TW555840B

Publication date: 2003-10-01

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Classification:

- international: B24B37/00; C09C1/68; C09G1/02; C09K3/14; H01L21/304; H01L21/306; H01L21/3205; H01L21/321; B24B37/00; C09C1/68; C09G1/00; C09K3/14; H01L21/02; (IPC1-7): C09K3/14

- European: C09G1/02

Application number: TW20020100316 20020111

Priority number(s): JP20010023316 20010131

Also published as:

EP1229093 (A1)
 US6679929 (B2)
 US2002139055 (A1)
 JP2002231666 (A)
 CN1369530 (A)

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Abstract of TW555840B

A polishing composition comprising the following components (a) to (g): (a) at least one abrasive selected from the group consisting of silicon dioxide, aluminum oxide, cerium oxide, zirconium oxide and titanium oxide, (b) an aliphatic carboxylic acid, (c) at least one basic compound selected from the group consisting of an ammonium salt, an alkali metal salt, an alkaline earth metal salt, an organic amine compound and a quaternary ammonium salt, (d) at least one polishing accelerating compound selected from the group consisting of citric acid, oxalic acid, tartaric acid, glycine, alpha-alanine and histidine, (e) at least one anticorrosive selected from the group consisting of benzotriazole, benzimidazole, triazole, imidazole and tolyltriazole, (f) hydrogen peroxide, and (g) water.

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US006679929B2

(12) **United States Patent**
Asano et al.

(10) Patent No.: **US 6,679,929 B2**
(45) Date of Patent: **Jan. 20, 2004**

(54) **POLISHING COMPOSITION AND
POLISHING METHOD EMPLOYING IT**

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(*) Notice: Subject to any disclaimer, the term of this
patent is extended or adjusted under 35
U.S.C. 154(b) by 57 days.

(21) Appl. No.: **10/046,394**

(22) Filed: **Jan. 16, 2002**

(65) **Prior Publication Data**

US 2002/0139055 A1 Oct. 3, 2002

(30) **Foreign Application Priority Data**

Jan. 31, 2001 (JP) 2001-023316

(51) Int. Cl.⁷ **C09G 1/02; C09G 1/04**

(52) U.S. Cl. **51/308; 51/307; 51/309;
106/3; 438/692; 438/693**

(58) **Field of Search** **51/307, 308, 309;
106/3; 438/692, 693**

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(57) **ABSTRACT**

A polishing composition comprising the following components (a) to (g):

- (a) at least one abrasive selected from the group consisting of silicon dioxide, aluminum oxide, cerium oxide, zirconium oxide and titanium oxide,
- (b) an aliphatic carboxylic acid,
- (c) at least one basic compound selected from the group consisting of an ammonium salt, an alkali metal salt, an alkaline earth metal salt, an organic amine compound and a quaternary ammonium salt,
- (d) at least one polishing accelerating compound selected from the group consisting of citric acid, oxalic acid, tartaric acid, glycine, α -alanine and histidine,
- (e) at least one anticorrosive selected from the group consisting of benzotriazole, benzimidazole, triazole, imidazole and tolyltriazole,
- (f) hydrogen peroxide, and
- (g) water.

13 Claims, No Drawings